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Recent results from the Berkeley 0.3-NA EUV microfield exposure tool

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Operating as a SEMATECH resist test center, the Berkeley 0.3-NA EUV microfield exposure tool¹ continues to play a crucial role in the advancement of EUV resists and masks. Here we present recent resist characterization results from the tool as well as tool characterization data. The tool-characterization data includes lithographic-based aberration measurements demonstrating the long-term stability of the tool.

Keywords: extreme ultraviolet, lithography, photoresist, resolution

References

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